

Title (en)

Semiconductor processing system and method for controlling moisture level therein

Title (de)

Anlage zur Behandlung von Halbleitern und Verfahren zur Steuerung der Feuchtigkeit darin

Title (fr)

Appareillage pour le traitement des semiconducteurs et méthode pour le réglage du niveau d'humidité à l'intérieure

Publication

EP 1195450 A3 20020612 (EN)

Application

EP 01402470 A 20010926

Priority

US 67788500 A 20001003

Abstract (en)

[origin: EP1195450A2] Provided is a novel semiconductor processing system. The system includes a process chamber for treating a semiconductor substrate with one or more process gases comprising water vapor, means for delivering the water vapor or one or more precursors thereof to the process chamber, an exhaust conduit connected to the process chamber, an absorption spectroscopy system for sensing water vapor in a sample region, and a control system which controls water vapor content in the process chamber. Also provided is a method for controlling the water vapor level in a semiconductor process chamber. The system and method allow for measurement and control of the water vapor level in a semiconductor processing chamber in which water vapor is present as a process gas. <IMAGE>

IPC 1-7

C23C 8/16; C30B 33/00; H01L 21/00; G01N 21/35

IPC 8 full level

G01N 21/3554 (2014.01); **C23C 8/16** (2006.01); **C30B 33/00** (2006.01); **H01L 21/02** (2006.01); **H01L 21/28** (2006.01); **H01L 21/285** (2006.01); **H01L 21/302** (2006.01); **H01L 21/3065** (2006.01); **H01L 21/31** (2006.01)

CPC (source: EP KR US)

C23C 8/16 (2013.01 - EP US); **C30B 33/005** (2013.01 - EP US); **H01L 21/02** (2013.01 - KR); **G01N 21/3554** (2013.01 - EP US)

Citation (search report)

- [AD] US 5963336 A 19991005 - MCANDREW JAMES [US], et al
- [A] US 5588831 A 19961231 - OKUYAMA SATORU [JP]
- [AD] US 5241851 A 19930907 - TAPP FREDERICK [US], et al
- [A] US 5652431 A 19970729 - DESISTO WILLIAM J [US], et al

Cited by

DE102008036050A1; EP2172766A1; EP1502289A4; EP1724567A1

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